

Comparative evaluation of porous PMO materials by PAS and EP

<u>A. G. Attallah,</u> A. S. Vishnevskiy, M. O. Liedke, E. Hirschmann, M. Butterling, D. S. Seregin, A. A. Rezvanov, K. A. Vorotilov, M. R. Baklanov, and A. Wagner



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Low – k dielectrics – the topic



- Scaling down:
 - Capacitance (C) increases
 - Resistance (R) of metal connectors
 - RC delay increases



Pradeep Kumar Singh, Ph.D. thesis, Chemnitz, 2013



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Low – k dielectrics – the topic



Challenge: reduction of signal delay, RC

Metal research

Low-k dielectrics research



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Low – k dielectrics – strategies





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Ultra - low - k dielectrics





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Motivation

- PAS and EP are only 2 techniques suitable for evaluation of thin films when the amount of materials is not sufficient for classical nitrogen porosimetry. This is the reason why both these techniques are used in nanoelectronics for evaluation of thin porous films.
- These techniques are based on completely different physical ideas. PAS measures reduction of Ps lifetime when they collide with pore wall, EP measures radius of curvature of a liquid condensed in the pores.
- This is the reason why cross evaluation of the obtained results is very important.



Experiment - Samples

Periodic mesoporous organosilicates (PMO)- based low-k



Experiment - Samples

The matrix composition was changed from pure methyl terminated (MTMS) to fully benzene bridged material





Experiment - PAS



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Experiment - EP



- Porosity and Pore size distribution
- Young Modulus
- Barrier integrity
- Sealing & Modification
- Plasma damage
- Swelling



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- > The peak at 1275 cm⁻¹ shows concentration of $-CH_3$ terminals (max in MTMS film)
- Two peaks at 1500-1600 cm⁻¹ are related to benzene bridge. (max in BTESB film)
- Benzene bridged films are not hydrophobic (water peaks at 3100-3700 cm⁻¹). Therefore, the presence of methyl terminals are important.





o-Ps lifetime measures 0.77 nm

matrix free volume in 100SB and

100MTMS samples

both samples have ~ 6% o-Ps

intensity in the matrix





o-Ps lifetime measures 0.77 nm

matrix free volume in 100SB and

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both samples have ~ 6% o-Ps
 intensity in the matrix

• the matrix free volumes

increased to ~ 1 nm when 30%

porogen was added

SB=25, 45% have the largest

free volumes

 I_{matrix} mirrors the change of I_{meso}

(see below)



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100SB and 100MTMS samples

have micropores before adding

porogen

size and I of 100SB are higher





100SB and 100MTMS samples have micropores before adding porogen size and I of 100SB are higher mesopores are the largest in **100MTMS** Transfor. of micro- to mesopores SB mesopores are smaller I_{meso} - 30% porogen \uparrow \rightarrow partial collaps of matrix to mesopores steep I_{meso} - SB-30% porogen

■ 100SB-30% porogen → denser



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Results – DB-PAS



3γ/2γ values → o-Ps escape (uncapped

samples)

Larger S.parameter in 100MTMC →

higher pore+defect conc. $(I_2+I_3+I_4)$



Results – DB-PAS



- 3γ/2γ values → o-Ps escape (uncapped samples)
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Value and shape of 3γ/2γ in 100MTMS 30 % porogen → open and intercon.

pores

Large S-paramter → big pores



Results – DB-PAS



- 3γ/2γ values → o-Ps escape (uncapped samples)
- Larger S.parameter in 100MTMC → higher pore+defect conc. $(I_2+I_3+I_4)$
- Value and shape of $3\gamma/2\gamma$ in 100MTMS-30 % porogen → open and intercon.

pores

- Large S-paramter → big pores
- $3\gamma/2\gamma$ of SB<MTMS \rightarrow less intercon. and

harder structure

■ S-parameter drops with SB→ total

defect conc. deceases with SB amount



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(the open porosity is varied in the range of 20-35%)



MTMS film has ink-bottle like shape, while other materials have cylindrical pores



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- Rapid drop in pore diameter is obtained when SB added
- Pore diameter slightly changes
 with increasing SB amount





Both methods show almost the

same behavior





- From EP
- Nonporous materials (blue) have higher Young's modulus (E) than porous
- E increases with SB concentration
- E stabilizes after SB= 60%



Summary

- PAS and EP cross evaluation of low-k films with different composition gave good agreement.
 Small difference in the pore size can be related to sidewall roughness and presence of adsorbed impurities. They can change Ps lifetime (PAS) and impact to the meniscus formation in EP.
- Both techniques showed that pure methyl terminated films have larger pore size. Introduction of 25-75% of BTESB reduces pore size to the value typical for pure benzene bridged films.
- It is shown that benzene bridged films are more hydrophilic and contain adsorbed moisture.
 This result allows to conclude that presence of methyl terminals are needed although the benzene bridged films have better mechanical properties.



Thank you for your attention!



Backup

EP is adsorption porosimetry

It uses Lorenz-Lorentz equation (1) to calculate porosity and Kelvin equation (4) to calculate pore size.

Full porosity:
$$V = 1 - \frac{B_p}{B_b} = 1 - \left[\frac{(n_p^2 - 1)}{n_p^2 + 2}\right] / \left[\frac{(n_s^2 - 1)}{(n_s^2 + 2)}\right]$$
 (1)

$$\tan \Psi \exp(i\Delta) = \frac{R^{P}}{R^{s}} \Rightarrow n, d$$

$$B = \sum_{i} \frac{4\pi N_{i}}{3} \alpha_{i} = V \frac{n_{1}^{2} - 1}{n_{1}^{2} + 2} + (1 - V) \frac{n_{2}^{2} - 1}{n_{2}^{2} + 2}$$

$$Pore interconnectivity: \quad x = V_{ads}/V$$

$$R = \frac{2\gamma V_{L}}{RT \ln(P/P_{0})}; \quad r = \frac{K}{4.574\sqrt{1/B}}$$

$$(2)$$

Pore size distribution: $dV_{ads}/dr vs. r$ (5)

Specific surface area:
$$\delta A_i = 2\delta V_i / r_i$$
; $A = \sum \delta A_i^p (m^2 / cm^3)$ (6)

 B_s is the volume of the film skeleton; B_p is the measured volume polarisability; V_m is the molecular volume of the adsorptive, α_{ads} is the polarisability adsorptive molecule; B_0 and d_0 are the volume polarisability and thickness of the film before adsorption, B_1 and d_1 are the volume polarisability and thickness of the film after adsorption



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